



***Batch-
Immersion
Processing
Efficiency with
NAURA Akrion
Reliability***

EFFICIENCY IN ACTION:

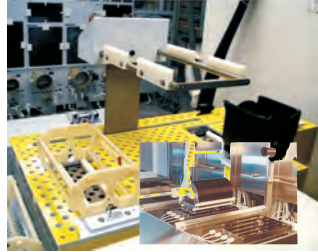
- Front End of Line Clean
(controlled concentrations from POR high to ultra-dilute)
- Back End of Line (BEOL) Clean - Side Wall Polymer Removal
- Etching & stripping applications
- Space saving multi-process tools
- Metal and Combination Wafer Reclaim
- 200 and 300mm Processing
- Small footprint, modular upgradability
preserves your investment
- Lowest Annual Consumable Parts Cost

***pre-diffusion clean
pre-gate clean
resist strip
nitride etch
BeOL Clean
wafer reclaim
photomask clean...***

applications solutions *developed for you*

ROBUST, POWERFUL CONTROL SOFTWARE

- NAURA Akrion control software (AKS v6) allows bi-directional processing
- Manual loading and SECS/GEM compliant factory automation support (e.g. SMIF, FOUP)
- Remote monitoring/editing support



ADVANCED TECHNOLOGY

LOW EXHAUST CLASS M1 MINI-ENVIRONMENT INSURES LOW PARTICLES

- High temperature and low temperature (Patent Pending) pre-epitaxial cleaning for silicon and Si:Ge wafers
- Precise concentration control
- Proprietary megasonics

FEOL CLEAN

- Particle Removal Efficiency > 97%
- Metal contamination < 7E9 atoms/cm² per element

BEOL CLEAN

- Systems for HDA- and Fluorine-based chemistries
- Proprietary in-line concentration control extends bath life and saves you money
- Proprietary (dualSWEEP™) ultrasonic technology



NITRIDE AND OXIDE ETCHING

- Footprint saving combination clean and etch stations for lower COO

RESIST STRIPPING

- Traditional sulfuric acid (piranha) configurations
- DIO3™ (ozonated DI water) for environmental concerns and lower COO with reduced chemical and disposal costs associated with H₂SO₄

NAURA AKRION RELIABILITY:

GAMA Systems in the hundreds are in place worldwide and overall reliability for the system exceeds 1500 hours mean time between failures (SEMI E10-96 MTBF). Coupled with the high yields associated with superior process results, GAMA saves you money.

CONTINUOUS IMPROVEMENT

THE NAURA AKRION WAY:

NAURA Akrion engineers respond to the needs of our customers with enhancements and upgrades to the GAMA system on a continual basis.

You can be assured that your GAMA will be able to run a new process if new needs arise. The modularity of the GAMA Series allows easy change-outs of modules in the field to preserve the useful lifetime of your purchase.

GAMA INNOVATION: The GAMAp_lus Advantage

GAMAp_lus in-situ modules are the latest in a long line of GAMA platform enhancements

- Replace dedicated rinse tanks for HF, SC1 and SC2 applications to minimize footprint & lower initial capital expense
- Minimize air interface for better particle performance
- Fresh, clean chemicals improve your process